

ABSTRACT

PRODUCTION METHOD FOR ETCHING LIQUID COMPOSITION

In one aspect, provided is a method for producing an etchant composition that is able to reduce dripping during the filling of a container with the etchant composition.

An aspect of the present disclosure relates to a method for producing an etchant composition. The etchant composition is used to etch a metal film that is disposed on a substrate. The method includes filling a container with the etchant composition by using a filling nozzle with a filling port through which the etchant composition is discharged. A receding contact angle of the etchant composition with respect to a raw material of the filling port of the filling nozzle is 60° or more, and the ratio of an advancing contact angle to a receding contact angle (advancing contact angle/receding contact angle) of the etchant composition is 1.4 or less.